



Molecular Imprints, Inc.

Contact Information:

Angela Ausman

1-512-334-1203

angela@molecularimprints.com

FOR RELEASE AUGUST 31, 2005

**MOLECULAR IMPRINTS GROWS ITS IP POSITION
WITH OVER 300 PATENT APPLICATIONS**

AUSTIN, TX, August 31, 2005 – Molecular Imprints, Inc. (MII), the world leader in S-FIL™ lithography, announces the filing of the 300th S-FIL related patent application worldwide. Presently, over 40 patents have been allowed or issued. MII believes it now has the largest nano-scale and 3D imprint patent portfolio of any company in the world, based on published patents.

MII continues to develop its Imprio® nano-lithography product line for numerous market opportunities. Intellectual property is a critical component of MII's business strategy. It also demonstrates the broad and deep technical capabilities of the Company.

Dr. S.V. Sreenivasan, MII's CTO, states, "These patent applications are related to all aspects of Molecular Imprints' proprietary S-FIL technology. In addition, many also address other forms of imprint lithography, and nano and 3D patterning in general."

Dr. Norm Schumaker, MII's CEO, said "This milestone is a testament to the hard work and drive of our technical staff and reflects our desire to protect our investor's equity going forward."

About Molecular Imprints Inc.

Molecular Imprints, Inc. (MII) is a global developer and manufacturer of nano-lithography systems for high resolution and for 3-dimensional pattern replication. The company has commercialized a proprietary imprint lithography technology (S-FIL), which is a room temperature, low pressure, non-contact-imprint process that has demonstrated sub-20 nanometer resolution. Molecular Imprints provides enabling lithography systems and technology for manufacturing applications in the areas of: nano-devices, magnetic data storage applications, solid state lighting, micro optical components, compound semiconductors and select silicon applications. For more information, visit: www.molecularimprints.com.

###